

# **VESTA and IPS Enter into Exclusive Agreement to Supply Atomic Layer Deposition Technology and Solution**

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VESTA Technology, Inc. (San Jose, Calif.) and Integrated Process Systems Ltd., a leading Korean manufacturer of semiconductor processing equipment have entered into an exclusive technology agreement for the marketing, sales, service and future development efforts focusing on the global Atomic Layer Deposition (ALD) market. VESTA will provide global support for IPS's product lines which include: ALD, Metal ALD/CVD, Multipole Inductively Coupled (MICP) Etch, and LCD Etch. This agreement also covers joint development efforts focusing on ALD technology and the delivery of Research and Development and production-proven processes for the deposition of thin films.

"ALD will be the key technology for nano-generations," said Chuck Kim, Executive Director, VESTA Technology. "Utilizing a showerhead and patented ozone process technology VESTA is well positioned to meet current and future process requirements for ALD applications. Our single-wafer technology overcomes the limitations of batch processing and provides key materials such as HfSiO<sub>x</sub> and barrier metals."

With an experienced team of semiconductor equipment industry veterans, VESTA is committed to the global sales, service and support of IPS's products. Ho-Seung Chang, CEO and president of IPS Ltd. states, "IPS's ALD business and technology will continue to grow in semiconductor high volume manufacturing production with our

exclusive license agreement with VESTA Technology, Inc."

The original press release is available [here](#).

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